

PATENT ABSTRACTS OF JAPAN

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(21)Application number : 02-273812

(71)Applicant : CANON INC

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(54) PRODUCTION OF FUNCTIONAL DEVICE

(57)Abstract:

PURPOSE: To inexpensively produce a functional device, where a thin functional film excellent in adhesive strength is formed on a base material, by previously deaerating a base material by holding this base material in a dry gas other than air, at the time of producing a functional device having a functional deposited film on a base material.

CONSTITUTION: For example, at the time of producing a functional device having a functional deposited film, such as information recording medium and semiconductor device, a gas which is composed of a gas other than air, such as O₂, N₂, and Ar, and in which concentration of contained moisture is regulated to ≤ 300 ppm on the basis of volume is introduced into a pretreatment chamber 1, where a base material 2 for device is placed on a supporting stand 6, through a gas introducing valve 4, allowed to reflux by means of a fan 3, and discharged through a gas discharge valve 5, by which the base material 2 is subjected to deaerating treatment. By using this deaerated base material, the thin functional film excellent in adhesive strength can be formed on the base material and the functional device excellent in stability can inexpensively be produced.

